

WHAT IS CLAIMED IS:

1. A method of cleaning a substrate for removing dirt on the substrate, comprising: irradiating a substrate surface with ultraviolet rays including
5 wavelengths of 184.9 nm and 253.7 nm in an oxygen-containing atmosphere, and then subjecting the substrate to wet cleaning with pure water.

2. A method according to claim 1, wherein said
10 oxygen-containing atmosphere comprises atmospheric air.

3. A method according to Claim 1, wherein said ultraviolet rays are generated from a discharge lamp.
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4. A method according to Claim 1, wherein said ultraviolet rays are generated from an excimer laser.

5. A method according to Claim 1, wherein said
20 ultraviolet rays are generated from a plurality of sources.

6. A method according to Claim 5, wherein at least one of the sources issues a wavelength selected
25 from 184.9 nm and 253.7 nm.

7. A method according to Claim 1, wherein at

least one of the wavelengths of 184.9 nm and 253.7 nm is a peak wavelength.

8. A method according to Claim 1, wherein the
5 substrate is irradiated with ultraviolet rays at an intensity of at least 0.2 J/cm^2 .

9. A method according to Claim 1, wherein the
substrate is subjected to the wet cleaning with pure
10 water within 30 min. after the irradiation with ultraviolet rays.

10. A method according to Claim 1, wherein said
substrate comprises a glass substrate.
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11. A method according to Claim 1, wherein the
substrate is subjected to the wet cleaning when the
substrate surface shows a contact angle with water of
at most 10 degrees after the irradiation with
20 ultraviolet rays.

12. A method according to Claim 1, wherein the
substrate comprises a substrate for a liquid crystal
device.
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13. A method according to Claim 1, wherein the
substrate comprises a glass substrate provided with a

transparent electrode.

14. A method according to Claim 13, wherein said transparent electrode comprises indium tin oxide.

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15. A method according to Claim 1, wherein the substrate after the wet cleaning is further irradiated with ultraviolet rays.

10 16. A method according to Claim 15, wherein the ultraviolet rays include wavelengths at 184.9 nm and 253.7 nm.

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